

This listing of claims will replace all prior versions of claims in the application.

Claim 1. (currently amended) A method for preparing a photoresist composition, comprising filtering a photoresist composition with a filter having a mean pore size of about 0.03 or less ~~less than about 0.40 micron~~.

Claim 2. (cancelled)

Claim 3. (original) The method of claim 1 wherein the filter comprises a polyamide filter membrane.

Claim 4. (cancelled) The method of claim 3 wherein the filter has a mean pore of about 0.03 or less.

Claim 5. (original) The method of claim 1 wherein the filter membrane comprises a polypropylene material.

Claim 6. (original) The method of claim 1 wherein the photoresist is a chemically-amplified positive resist composition.

Claim 7. (currently amended) A method for preparing a photoresist composition, comprising filtering a photoresist composition through a filter having a pore size of about 0.03 or less ~~less than about 0.4 microns~~.

Claim 8. (original) The method of claim 7 wherein the filter membrane comprises a Nylon material.

Claim 9. (cancelled)

Claim 10. (original) The method of claim 7 wherein the filter membrane comprises a polypropylene material.

Claim 11. (currently amended) A method for preparing an organic antireflective coating composition for use with an overcoated photoresist composition, comprising filtering an organic coating composition with a filter having a mean pore size of about 0.03 or less ~~less than about 0.4 microns~~.

Claim 12. (original) The method of claim 11 wherein the filter membrane comprises a Nylon material.

Claim 13. (original) The method of claim 12 wherein the filter has a mean pore size of about 0.03 microns or less.

Claim 14. (original) The method of claim 12 wherein the filter has a mean pore size of about 0.02 microns or less.

Claims 15-18. (cancelled)

Claim 19. (new) The method of claim 1 wherein the filter has a mean pore size of about 0.025 microns or less.

Claim 20. (new) The method of claim 1 wherein the filter has a mean pore size of about 0.02 microns or less.

Claim 21. (new) The method of claim 7 wherein the filter has a mean pore size of about 0.025 microns or less.

Claim 22. (new) The method of claim 7 wherein the filter has a mean pore size of about 0.02 microns or less.

Claim 23. (new) The method of claim 11 wherein the filter has a mean pore size of about 0.025 microns or less.

Claim 24. (new) The method of claim 11 wherein the filter has a mean pore size of about 0.02 microns or less.

Claim 25. (new) The method of claim 1 wherein the photoresist is passed through the filter more than 20 times.

Claim 26. (new) The method of claim 11 wherein the antireflective coating composition is passed through the filter more than 20 times.